**PATENT** 

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Klaus Florian Schuegraf et al.

Examiner: Ori Nadav

Serial No.:

08/902,809

Group Art Unit: 2811

Filed:

July 30, 1997

Docket: 303.278US1

Title:

SELECTIVE SPACER TECHNOLOGY TO PREVENT METAL OXIDE

FORMATION DURING POLYCIDE REOXIDATION

11/a FJ 0-23-98

## **AMENDMENT AND RESPONSE**

Assistant Commissioner for Patents Washington, D.C. 20231

In response to the Office Action mailed June 9, 1998, to which a one month extension of time has been obtained, please amend the above-identified application as follows:

## IN THE TITLE

Please replace the title with the following new title: --Selective Spacer To Prevent Metal Oxide Formation During Polycide Reoxidation--.

## IN THE SPECIFICATION

On page 4, line 22, change "nitride" to --polysilicon, a refractory metal, and a dielectric--.

On page 4, line 26, change "refractory metal 205" to --refractory metal of electrode 205--.

On page 5, line 3, change "polycide reoxidation" to -- polycide reoxidation 220--.

On page 5, line 6, change "reoxidized" to --reoxidized 220--.

On page 5, line 9 change "metal layers 205" to --metal layers--.

On page 5, line 13, change "undoped silicon" to --undoped silicon 211 with reoxidation 221--.

## IN THE ABSTRACT

Please replace the abstract with a new abstract attached hereto as a separate page.